

Electronic Supplementary Information

Photoinduced Synthesis and Ordering of Lamellar *n*-Alkylsiloxane Films

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Sample	T ¹ (mol%)	T ² (mol%)	T ³ (mol%)	Molar ratio (OH / Si)
C ₈ PS	0	44	56	0.44
C ₁₀ PS	1	46	53	0.48
C ₁₂ PS	2	47	51	0.51
C ₁₆ PS	8	64	28	0.8
C ₁₈ PS	11	62	27	0.84

Table S1 Proportion of siloxane subspecies and silanol functions in *n*-alkylsiloxane films synthesized *via* sol-gel photopolymerization

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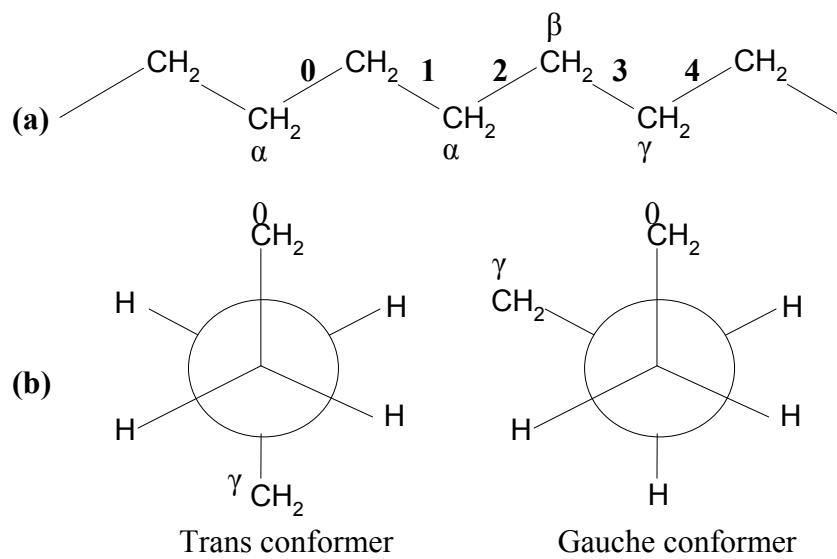


Fig. S1 (a) Portion of the interior methylene groups of an alkyl chains in all-trans, planar zigzag conformation. (b) Newman projections along the C-C bond **2** illustrating trans and gauche conformers

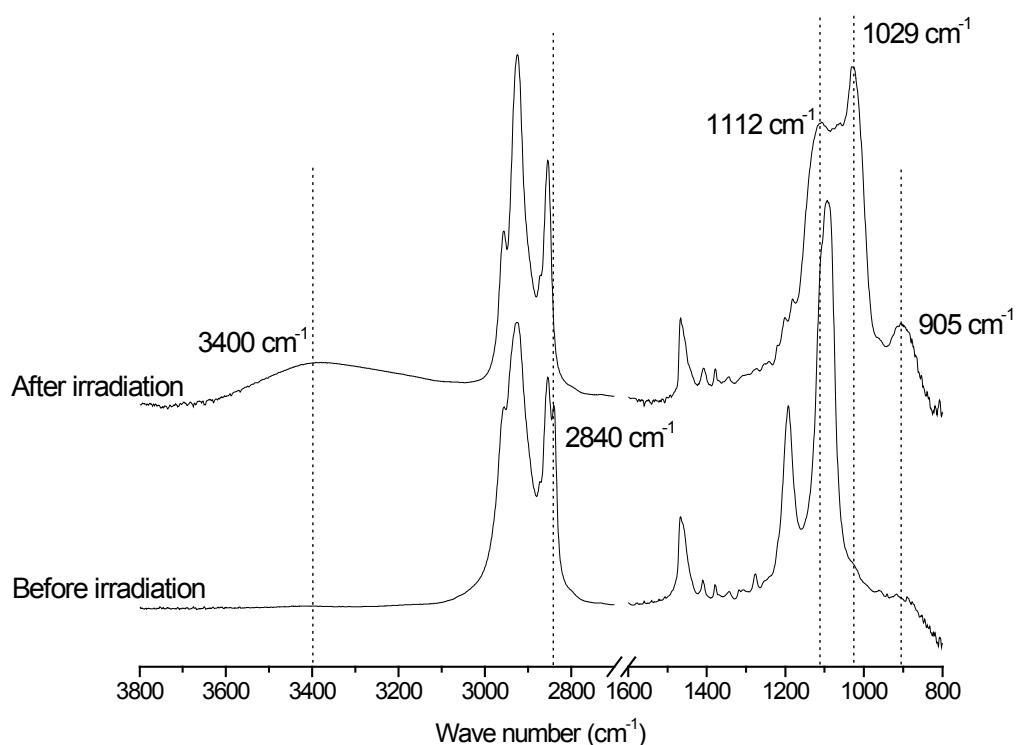


Fig. S2 FTIR spectra of C₁₀TMS film before and after irradiation

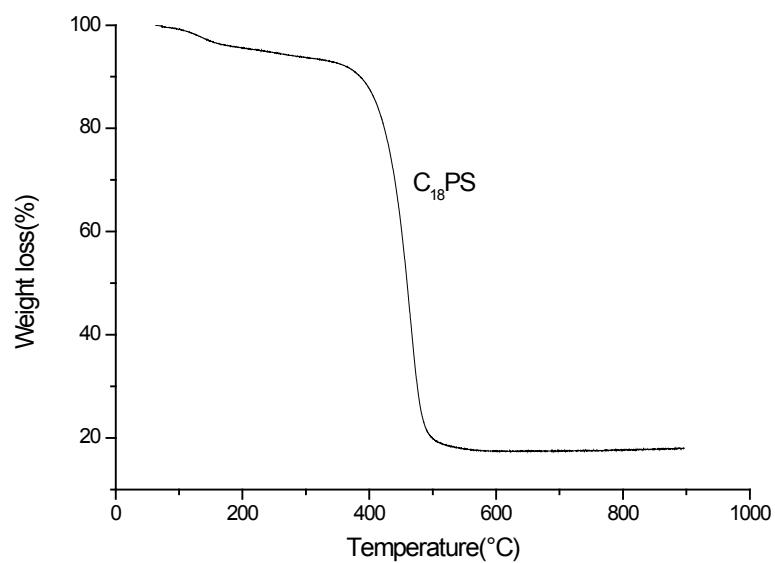
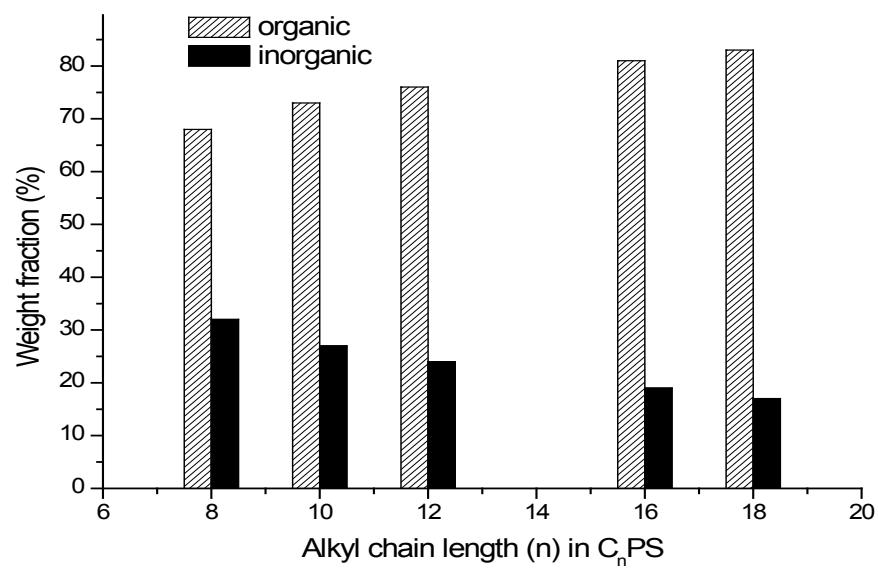


Fig. S3 Proportion of organic and inorganic moieties in C_nPS films (up). Thermal gravimetric plot of $C_{18}PS$ (down).